Al_2O_3-ZnO Target : AZO, AZO-H
Ga_2O_3-ZnO Target : GZO

Sputtering Target for TCO film of photovoltaic solar cell

太阳能电池的透明导电膜用溅射靶材

< Material >

AZO and AZO-H : Al_2O_3 wt% can be controlled.
GZO : Ga_2O_3 wt% can be controlled.

AZO-H, GZO is
- less number of arcing during sputtering times than AZO.
- lower resistivity than AZO.

< Film >

GZO film is lowest resistivity than AZO and AZO-H

PRODUCT DESCRIPTION

Applications	Transparent Conductive Oxide films of solar cells Optical films of PDP
用途	太阳能电池用透明导电膜 PDP用光学膜

＜材料＞
成份易于变更。
AZO-H、GZO比AZO击穿少，比AZO电阻低。

＜膜＞
GZO膜比AZO膜、AZO-H膜电阻低。

AGC Ceramics Co.,LTD.

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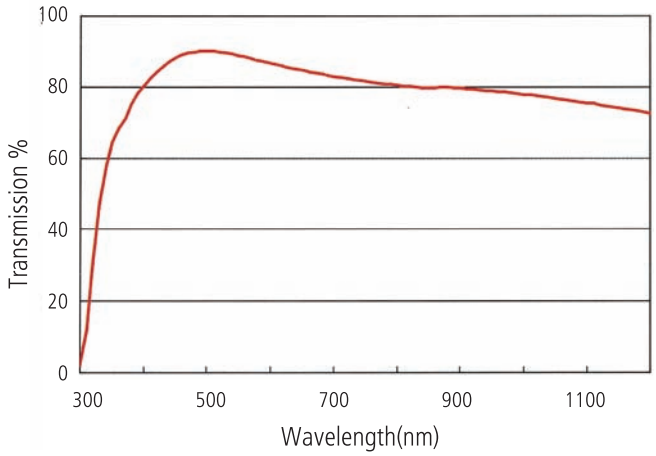
Feb. 2011

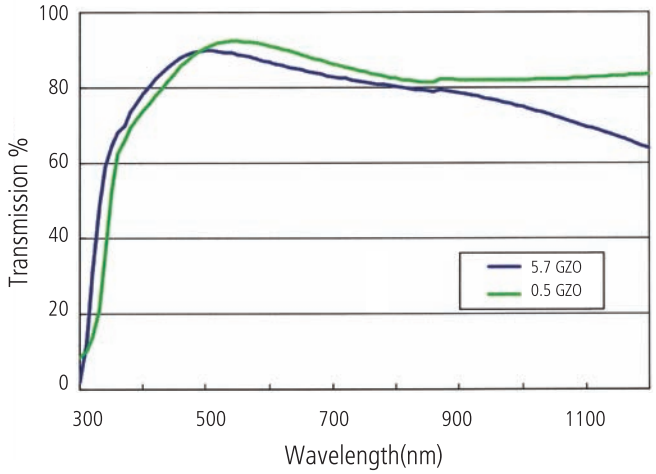
Transmission

AZO and AZO-H



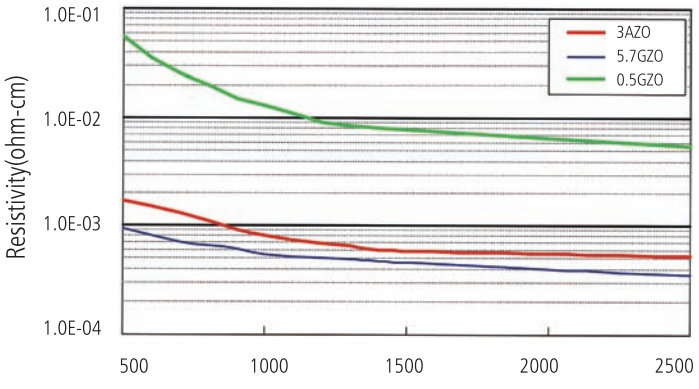
*) Film thickness of 130nm on the soda glass

GZO



*) Film thickness of 130nm on the soda glass

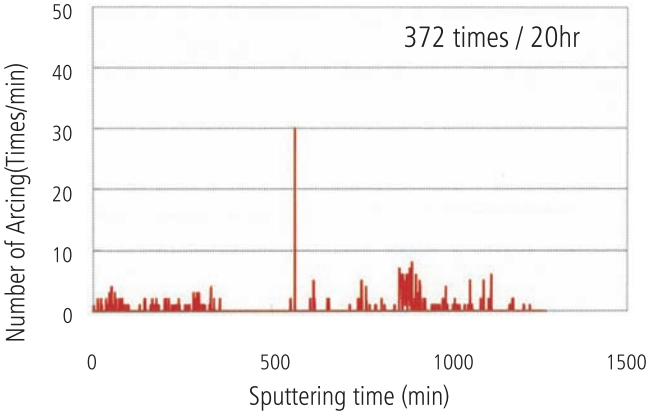
Electrical property



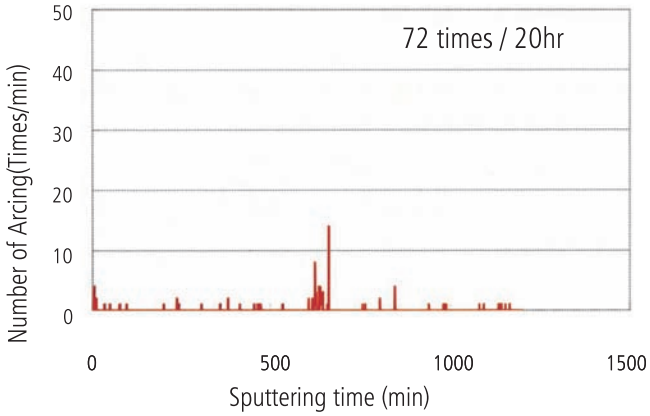
*) Films were deposited on the glass at 200℃.

Stability of sputtering times

AZO



AZO –H



GZO